What is claimed is:

1. A composition for removing a film resist wherein the composition comprises:

about 2-55% by weight of at least one alkanolamine or at least one morpholine or mixtures thereof based on the total weight of the composition;

about 20-94% by weight of at least one organic solvent based on the total weight of the composition; and

about 0.5-60% by weight water based on the total weight of the composition.

2. The composition of claim 1 further comprising:

about 0.1% to about 10% of one or more hydroxides; and

about 0.5 to about 10% of one or more corrosion inhibitors.

3. The composition of claim 1 comprising:

about 15-20% by weight of said at least one alkanolamine or at least one morpholine or mixtures thereof;

about 40-65% by weight of said at least one organic solvent; and

about 10-40% by weight said water;

and further comprising about 0.1-5% by weight of at least one hydroxide;

and at least one corrosion inhibitor.

4. The composition of claim 1 comprising:

about 2-30% by weight of said at least one alkanolamine or at least one morpholine or mixtures thereof;

about 40-90% by weight of said at least one organic solvent; and

about 10-40% by weight said water;

and further comprising about 0.1-5% by weight of at least one hydroxide;

and about 1-5.5% by weight of at least one corrosion inhibitor.

5. The composition of claim 1 comprising:

about 2-10% by weight of said one or more alkanolamines or one or more morpholines or mixtures thereof;

about 65-90% by weight of the one or more organic solvents;

about 2-17% by weight water;

and further comprising about 0.05-4% of said one or more hydroxides; and

about 0.5-2% by weight of one or more corrosion inhibitors based on the total weight of the composition.

6. The composition of claim 1 further comprising a hydroxide.

7. The composition of any one of claims 2 to 6, wherein the hydroxide is potassium hydroxide.

8. The composition of claim 2 to 8, wherein the hydroxide comprises a quaternary compound.

9. The composition of claim 1 further comprising a corrosion inhibitor.

10. The composition of any one of claims 2 to 9, wherein the corrosion inhibitor selected from the group consisting of thiazoles, organic acid salts, phenols, acids, triazoles, catechol, resorcinol, maleic anhydride, phthalic anhydride, catechol, pyrogallol, esters of gallic acid, carboxybenzotriazole, fructose, ammonium thiosulfate, glycine, tetramethylguanidine, iminodiacetic acid, dimethylacetoacetamide, trihydroxybenzene, dihydroxybenzene, salicyclohydroxamic, aminobenzosulfonic acid and mixtures thereof.

11. The composition of claim 10, wherein the thiazole is aminobenzothiazole.

12. The composition of claim 1, wherein the composition comprises:

about 10-20% by weight of the alkanolamine based on the total weight of the composition;

about 50-75% by weight of the organic solvent based on the total weight of the composition;

about 0-1.5% by weight of a thiazole or imidazole based on the total weight of the composition;

about 0-5% by weight of a hydroxide based on the total weight of the composition; and

about 0.5-60% by weight water based on the total weight of the composition

13. The composition of claim 1, wherein the composition comprises:

about 10-20% by weight of the alkanolamine based on the total weight of the composition;

about 50-75% by weight of the organic solvent based on the total weight of the composition;

about 0.1-1.5% by weight of a thiazole, or imidazole based on the total weight of the composition;

about 0.1-2% by weight of potassium hydroxide based on the total weight of the composition; and

remainder water based on the total weight of the composition

14. The composition of any one of claims 1 to 13, wherein the at least one alkanolamine comprises monoethanol amine, N-methylethanolamine, or triethanolamine.

15. The composition of any one of claims 1 to 14, wherein the at least one organic solvent is selected from the group consisting of glycol ethers and hydric alcohols or diols having 2 to 8 carbon atoms.

16. The composition of any one of claims 1 to 15, wherein the at least one organic solvent comprises tetrahydrofufuryl alcohol.

17. The composition of any one of claims 1 to 16, where the at least one organic solvent comprises tri(propylene glycol) methyl ether.

18. The composition of any one of claims 1 to 17, wherein the composition is free of dimethyl acetamide.

19. The composition of any one of claims 1 to 18, wherein the composition is free of dimethylsulfoxide or N-methylpyrrolidone.

20. The composition of any one of claims 1 to 5 and 12 and 13 being substantially free of one or more of the following in any combination: dimethyl acetamide, quaternary hydroxides, potassium hydroxide or other metal hydroxide, fluorine, chlorine, oxidizer, H_2O_2 or nitric oxide.

21. The composition of any one of claims 1 to 5 and 12 and 13 being substantially free of all of the following: dimethyl acetamide, fluorine, chlorine, oxidizer, H2O2 or nitric oxide.

22. The composition of any one of claims 1 to 21 further comprising an organic acid selected from the group consisting of citric acid, anthranilic acid, gallic acid, benzoic acid, malonic acid, maleic acid, fumaric acid, D,L-malic acid, isophthalic acid, phthalic acid, lactic acid, tannic acid and mixtures thereof.

23. The composition of any one of claims 1 to 22, wherein the composition has a pH of about 8.0 or higher.

24. A composition suitable for removing a film resist consisting essentially of:

about 5-30% by weight of an alkanolamine based on the total weight of the composition;

about 20-80% by weight of a water soluble or water miscible organic solvent, which is not dimethyl acetamide, dimethylsulfoxide, or N-methylpyrrolidone, based on the total weight of the composition;

about 0.1-1.5% by weight of a corrosion inhibitor based on the total weight of the composition;

about 0.1-2% by weight of a hydroxide, which is not a quaternary compound, based on the total weight of the composition;

about 0-5% by weight of an organic acid based on the total weight of the composition; and

about 0.5-60% by weight water based on the total weight of the composition.

25. The composition of any one of claims 2 to 5 wherein the alkanolamine is monoethylamine, or the morpholine is N-(3-aminopropyl) morpholine; the solvent is selected from the group consisting of tetrahydrofufuryl alcohol, dimethylsulfoxide, tri(propylene glycol)methyl ether; propylene glycol monophenyl ether, dipropylene glycol, benzyl alcohol, and mixtures thereof; and the corrosion inhibitor is selected from the group consisting of 2-aminobenzothiazole, isophthalic acid, t-butylcatechol, 2-mercaptobenzimidazole and mixtures thereof.

26. The composition of any one of claims 2 to 5, wherein the alkanolamine is monoethylamine, the solvent is selected from the group of tetrahydrofufuryl alcohol, dimethylsulfoxide, tri(propylene glycol)methyl ether; the corrosion inhibitor is selected from the

group consisting of 2-aminobenzothiazole, isophthalic acid, t-butylcatechol, 2-mercaptobenzimidazole and mixtures thereof, and the hydroxide is selected from the group consisting of potassium hydroxide and choline hydroxide and mixtures thereof.

27. The composition of any one of claims 1 to 5, wherein the morpholine is N-(3-aminopropyl) morpholine; and the solvent is selected from the group consisting of propylene glycol monophenyl ether, dipropylene glycol, tripropylene glycol monomethyl ether, benzyl alcohol, and dipropylene glycol and mixtures thereof.

28. A method of stripping a film resist comprising:

applying to the film resist the composition of any of claims 1-27.

29. The method of claim 28 wherein the film resist has a thickness of up to about 150 μm.

CLAIMS

1. A composition for removing a film resist wherein the composition comprises:

   2-55% by weight of at least one alkanolamine or at least one morpholine or mixtures thereof based on the total weight of the composition;

   20-94% by weight of at least one organic solvent based on the total weight of the composition;

   0.5-60% by weight water based on the total weight of the composition;

   0.1% to 10% of potassium hydroxide based on the total weight of the composition; and

   0.5 to 10% of one or more corrosion inhibitors based on the total weight of the composition, wherein the composition is free of dimethylsulfoxide or N-methylpyrrolidone.

2. The composition of claim 1 further comprising:

   at least one quaternary ammonium hydroxide selected from the group consisting of choline hydroxide, tetramethylammonium hydroxide, and tetraethylammonium hydroxide.

3. The composition of claim 1 comprising:

   15-20% by weight of said at least one alkanolamine or at least one morpholine or mixtures thereof;

   40-65% by weight of said at least one organic solvent;

   10-40% by weight said water; and

   0.1-5% by weight of said potassium hydroxide.

4. The composition of claim 1 comprising:

   2-30% by weight of said at least one alkanolamine or at least one morpholine or mixtures thereof;

   40-90% by weight of said at least one organic solvent;

   10-40% by weight said water;

   0.1-5% by weight of said potassium hydroxide;

   and 1-5.5% by weight of said at least one corrosion inhibitor.

5. The composition of claim 1 comprising:

   2-10% by weight of said one or more alkanolamines or one or more morpholines or mixtures thereof;

65-90% by weight of the one or more organic solvents;
2-17% by weight water;
0.05-4% of said potassium hydroxide; and
0.5-2% by weight of said one or more corrosion inhibitor.

6. The composition of claim 1, wherein the at least one alkanolamine comprises monoethanol amine, N-methylethanolamine, or triethanolamine.

7. The composition of claim 1, wherein the at least one organic solvent is selected from the group consisting of glycol ethers and hydric alcohols or diols having 2 to 8 carbon atoms.

8. The composition of claim 1, wherein the at least one organic solvent comprises tetrahydrofurfuryl alcohol.

9. The composition of claim 1, where the at least one organic solvent comprises tri(propylene glycol) methyl ether.

10. The composition of claim 1, wherein the composition is free of dimethyl acetamide.

11. The composition of claim 2, wherein the quarternary hydroxide comprises choline hydroxide or tetramethylammonium hydroxide.

12. The composition of claim 1 being substantially free of all of the following: dimethyl acetamide, fluorine, chlorine, oxidizer, H_2O_2 or nitric oxide.

13. The composition of claim 1 wherein the corrosion inhibitor is selected from the group consisting of thiazoles, organic acid salts, phenols, acids, triazoles, catechol, resorcinol, maleic anhydride, phthalic anhydride, catechol, pyrogallol, esters of gallic acid, carboxybenzotriazole, fructose, ammonium thiosulfate, glycine, tetramethylguanidine, iminodiacetic acid, dimethylacetoacetamide, trihydroxybenzene, dihydroxybenzene, salicyclohydroxamic, aminobenzosulfonic acid and mixtures thereof.

14. The composition of claim 13, wherein the thiazole is aminobenzothiazole.

15. The composition of claim 14 further comprising an organic acid selected from the group consisting of citric acid, anthranilic acid, gallic acid, benzoic acid, malonic acid, maleic acid, fumaric acid, D,L-malic acid, isophthalic acid, phthalic acid, lactic acid, tannic acid and mixtures thereof.

16. The composition of claim 1, wherein the composition has a pH of 8.0 or higher.

17. The composition of claim 1, wherein the composition comprises:

10-20% by weight of the alkanolamine;

50-75% by weight of the organic solvent;

0-1.5% by weight of a thiazole or imidazole;

0-5% by weight of potassium hydroxide; and

0.5-60% by weight water.

18. The composition of claim 1, wherein the composition comprises:

10-20% by weight of the alkanolamine;

50-75% by weight of the organic solvent;

0.1-1.5% by weight of a thiazole or imidazole;

0.1-2% by weight of potassium hydroxide; and

remainder water.

19. A composition suitable for removing a film resist consisting essentially of:

5-30% by weight of an alkanolamine based on the total weight of the composition;

20-80% by weight of a water soluble or water miscible organic solvent, which is not dimethyl acetamide, dimethylsulfoxide, or N-methylpyrrolidone, based on the total weight of the composition;

0.1-1.5% by weight of a corrosion inhibitor based on the total weight of the composition;

0.1-2% by weight of potassium hydroxide, based on the total weight of the composition;

0-5% by weight of an organic acid based on the total weight of the composition; and

0.5-60% by weight water based on the total weight of the composition, wherein the composition is free of dimethylsulfoxide or N-methylpyrrolidone.

20. The composition of claim 1 wherein the alkanolamine is monoethanolamine, the solvent is tetrahydrofufuryl alcohol, the corrosion inhibitor is 2-aminobenzothiazole, and the hydroxide is potassium hydroxide.

21. The composition of claim 2, wherein the alkanolamine is present and is monoethanolamine, the solvent is selected from the group of tetrahydrofurfuryl alcohol, dimethylsulfoxide, tri(propylene glycol)methyl ether; the corrosion inhibitor is selected from the group consisting of 2-aminobenzothiazole, isophthalic acid, t-butylcatechol, 2-mercaptobenzimidazole and mixtures thereof, and the quaternary ammonium hydroxide is choline hydroxide.

22. The composition of claim 5, wherein the morpholine is selected and is N-(3-aminopropyl) morpholine; and the solvent is selected from the group consisting of propylene glycol monophenyl ether, dipropylene glycol, tripropylene glycol monomethyl ether, benzyl alcohol, and dipropylene glycol and mixtures thereof.

23. A method of stripping a film resist comprising:
applying to the film resist a composition according to claim 1.

24. The method of claim 23 wherein the film resist has a thickness of up to 150 μm.